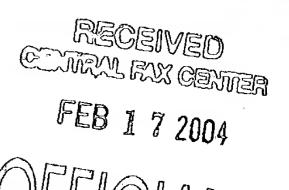
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Mayer, Fortkort & Williams, PC Attorneys At Law

13164 Lazy Glen Lane Oak Hill, Virginia 20171

Westfield, NJ 07090

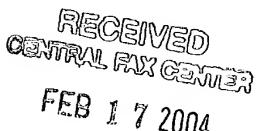
251 North Avenue West, 2<sup>nd</sup> Floor





To:	Com	missioner for Paten	ls	Promi		vid Bonham 03) 433-0510
Fax:	703-872-9310			Total pages: 13		
Phone:				Date:	2/1	17/2004
Re:	In connection with prosecution in Serial. No. 09/905,172, please find enclosed an Amendment CC: and Response to the Office Action mailed November 14, 2003.					
	Dav	id Bonham				
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Serial No. 09/905,172



## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:

David S. Mui et al.

Serial No.:

09/905,172

Filed:

07/13/2001

Title:

ETCH PATTERN DEFINITION USING A CVD ORGANIC LAYER AS AN

ANTI-REFLECTION COATING AND HARDMASK

Art Unit:

1765

Examiner:

Deo, Duy Vu Nguyen

Docket No.:

004227USA02/ETCH/SILICON

VIA FACSIMILE 703-872-9310 Mail Stop Non Fee Amendment Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

## **AMENDMENT AND RESPONSE**

Sir:

Responsive to the Office Action mailed November 14, 2003 in the above matter (the 3-month period for reply extended to February 17, 2004 due to the PTO holiday closing on 2/16/04), Applicants submit the following amendment and remarks: